

ABSTRACTSUBSTRATE LOADING APPARATUS

5       The present invention provides apparatus for loading  
a substrate (65) onto a processing surface (61) in a thin-  
film processing chamber (60). The apparatus includes a  
support (66) which cooperates with one or more  
10       corresponding apertures (62) in the processing surface so  
as to be movable between an extended position in which the  
support can support a substrate (65) above the processing  
surface (61), and a retracted position in which the support  
is flush with or located below the processing surface (61).  
The support has a number of limbs (64) which extend  
15       radially outwardly from a central hub, at an angle relative  
to the processing surface. The limbs contact the edges of  
different sized substrates in use so as to support the  
substrate in a support plane above the central hub and  
substantially parallel to the processing surface.